

# **Introduction to Modeling MOSFETS in SPICE**

**By: Mr. C. ZIGHA**

## **OUTLINE**

Introduction  
MOSFET SPICE  
Shichman and Hodges Model  
MOSFET Attributes  
Ids-Vds Family of Curves  
Ids-Vgs  
Conclusion  
References

## ***INTRODUCTION***

PSpice Lite 9.2 is one of the OrCAD family of products, from Cadence Design Systems, Inc., offering a complete suite of electronic design tools.

It is free and includes limited versions of OrCAD Capture, for schematic capture, PSpice for analog circuit simulation and Pspice A/D for mixed analog and digital circuit simulation.

PSpice Lite 9.2 is limited to 64 nodes, 10 transistors, two operational amplifiers and 65 primitive digital devices. See page 35 (xxxv) of the PSpice Users Guide.

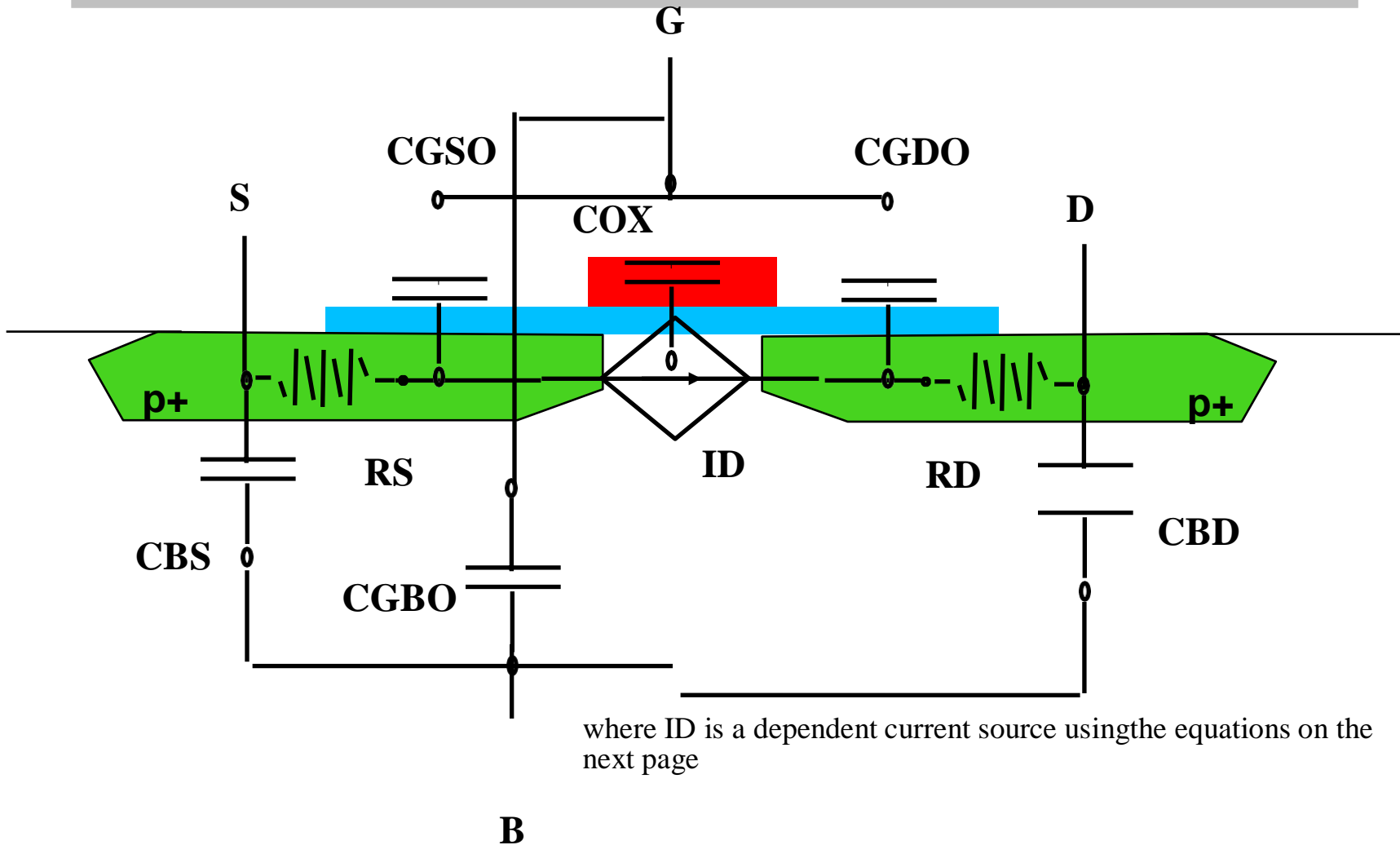
LT SPICE – is a free SPICE simulator with schematic capture from Linear Technology. It is quite similar to PSpice Lite but is not limited in the number of devices or nodes. Linear Technology (LT) is one of the industry leaders in analog and digital integrated circuits. Linear Technology provides a complete set of SPICE models for LT components.

## ***MOSFET DEVICE MODELS***

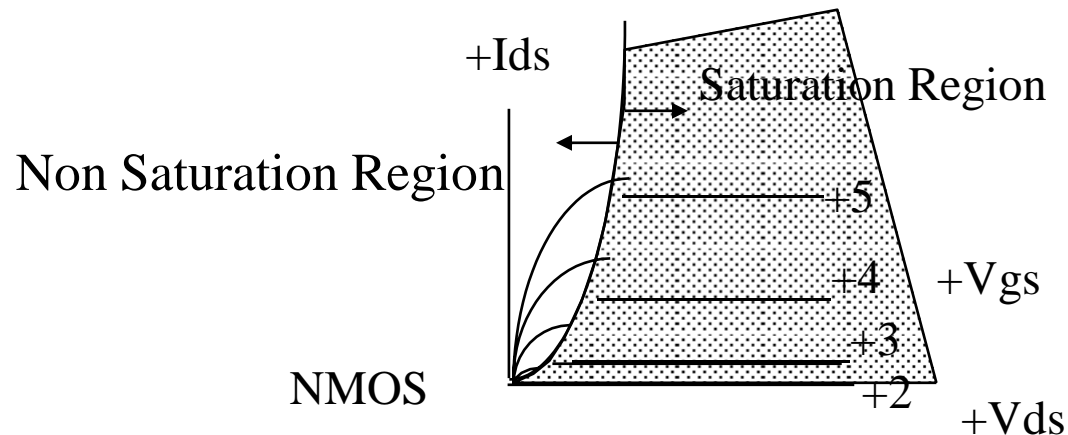
MOSFET Device models used by SPICE (Simulation Program for Integrated Circuit Engineering) simulators can be divided into three classes: First Generation Models (Level 1, Level 2, Level 3 Models), Second Generation Models (BISM, HSPICE Level 28, BSIM2) and Third Generation Models (BSIM3, Level 7, Level 8, Level 49, etc.) The newer generations can do a better job with short channel effects, local stress, transistors operating in the sub-threshold region, gate leakage (tunneling), noise calculations, temperature variations and the equations used are better with respect to convergence during circuit simulation.

In general first generation models are recommended for MOSFETs with gate lengths of 10 $\mu$ m or more. If not specified most SPICE MOSFET Models default to level=1 (Shichman and Hodges)

# SPICE LEVEL-1 MOSFET MODEL



# SPICE LEVEL 1 - SHICHMAN AND HODGES



$$I_{Dsat} = \frac{\mu W C_{ox'} (V_g - V_t)^2}{2L}$$

Saturation Region

$$I_D = \frac{\mu W C_{ox'}}{L} (V_g - V_t - V_d/2) V_d$$

Non Saturation Region

where  $\mu$ ,  $C_{ox'}$  and  $V_t$  are given in equations on the next pages

# SPICE LEVEL-1 EQUATIONS FOR UO, VTO AND COX'

Mobility:  
(cm<sup>2</sup>/V-s)

$$\mu = \mu_{\min} + \frac{(\mu_{\max} - \mu_{\min})}{\{1 + (N/N_{\text{ref}})^{\alpha}\}}$$

Parameter	Arsenic	Phosphorous	Boron
$\mu_{\min}$	52.2	68.5	44.9
$\mu_{\max}$	1417	1414	470.5
$N_{\text{ref}}$	$9.68 \times 10^{16}$	$9.20 \times 10^{16}$	$2.23 \times 10^{17}$
$\alpha$	0.680	0.711	0.719

Threshold Voltage:  
+/-  
nmos/pmos

$$V_{\text{TO}} = \Phi_{\text{ms}} - q \text{NSS}/C_{\text{ox}}' \pm 2[\Phi_{\text{F}}] \pm 2 (q\epsilon_0\epsilon_{\text{rsi}} \text{NSUB} [\Phi_{\text{F}}])^{0.5}/C_{\text{ox}}'$$

$$[\Phi_{\text{F}}] = (KT/q) \ln (\text{NSUB}/n_i) \quad \text{where } n_i = 1.45 \times 10^{10} \text{ and } KT/q = 0.026$$

Absolute value

Gate Capacitance  
per unit area  $C_{\text{ox}}'$

$$C_{\text{ox}}' = \epsilon_{\text{rox}} \epsilon_0 / \text{TOX} = 3.9 \epsilon_0 / \text{TOX}$$

$$\text{PHI} = 2 [\Phi_{\text{F}}]$$

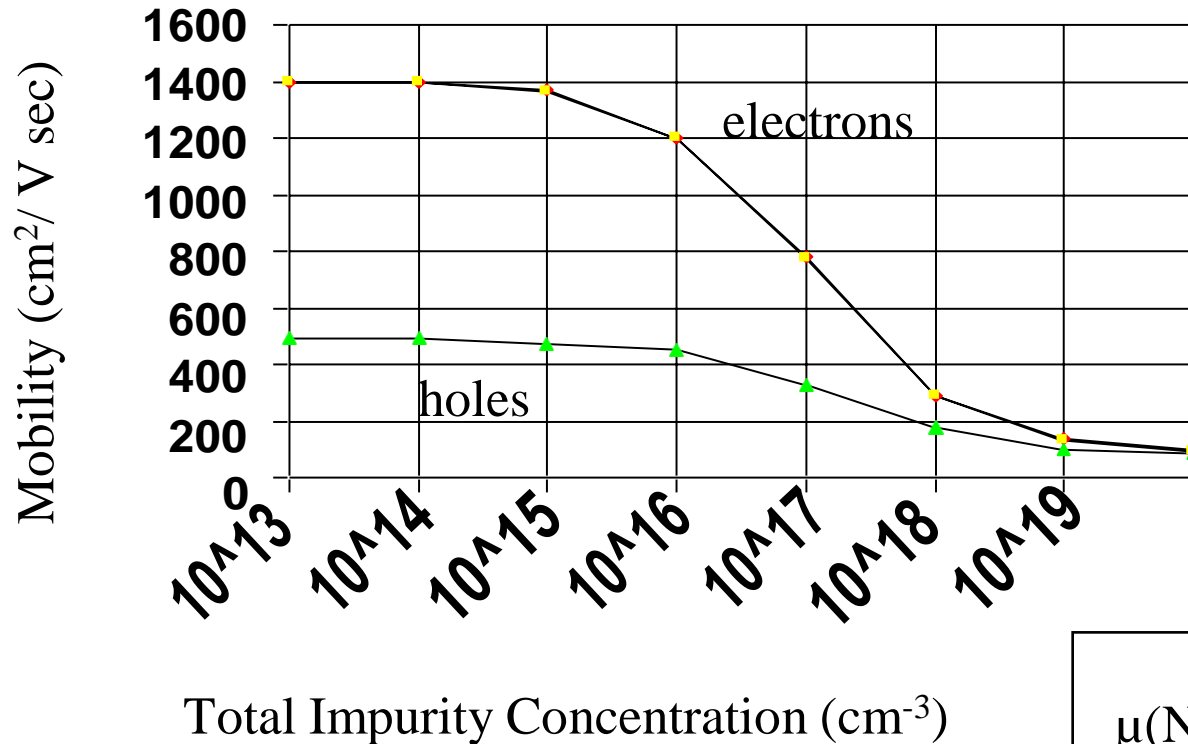
$$= 3.9$$

where  $\epsilon_{\text{rsi}} = 11.7$  and  $\epsilon_{\text{rox}}$

$$\epsilon_0 = 8.85 \times 10^{-12} \text{ F/m or } 8.8 \times 10^{-14} \text{ F/cm}$$

$$q = 1.6 \times 10^{-19}$$

# MOBILITY MODEL



Electron and hole mobilities in silicon at 300 K as functions of the total dopant concentration (N). The values plotted are the results of the curve fitting measurements from several sources. The mobility curves can be generated using the equation below with the parameters shown:

$$\mu(N) = \mu_{mi} + \frac{(\mu_{\max} - \mu_{\min})}{\{1 + (N/N_{\text{ref}})^{\alpha}\}}$$

# LONG CHANNEL THRESHOLD VOLTAGE, $V_T$

**Flat-band Voltage**  $V_{FB} = \phi_{ms} - \frac{Q_{ss}}{C'_{ox}} - \frac{1}{C'_{ox}} \int_0^{X_{ox}} \frac{X \rho(x)}{X_{ox}} dx$

p-type substrate  
(n-channel)

n-type substrate  
(p-channel)

$$Q_{ss} = q N_{ss}$$

**Bulk Potential :**  $\phi_p = -KT/q \ln (N_A/n_i)$

$\phi_n = +KT/q \ln (N_D/n_i)$

**Work Function Difference**  $\phi_{MS} = \phi_M - (X + E_g/2q + [\phi_p])$

$\phi_{MS} = \phi_M - (X + E_g/2q - [\phi_n])$

**Maximum Depletion Width:**  
( $W_{dmax}$ )  $\sqrt{\frac{4 \epsilon_s [\phi_p]}{q N_A}}$

$\sqrt{\frac{4 \epsilon_s [\phi_n]}{q N_D}}$

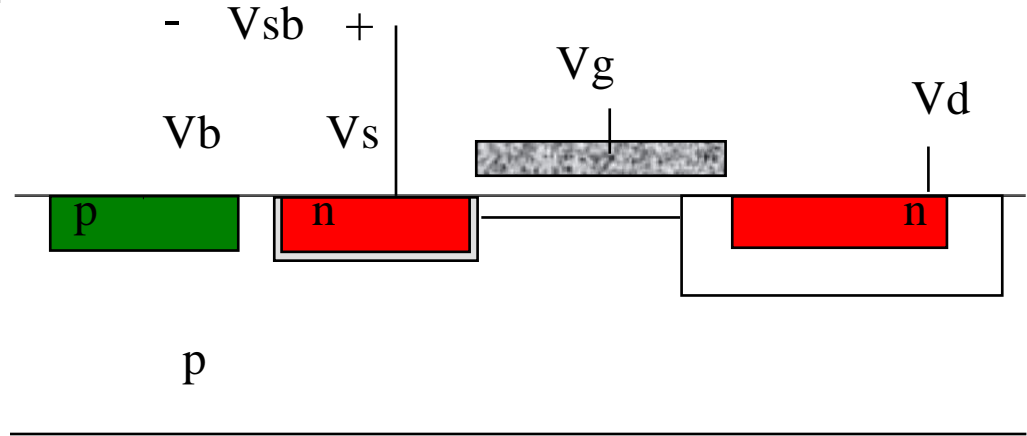
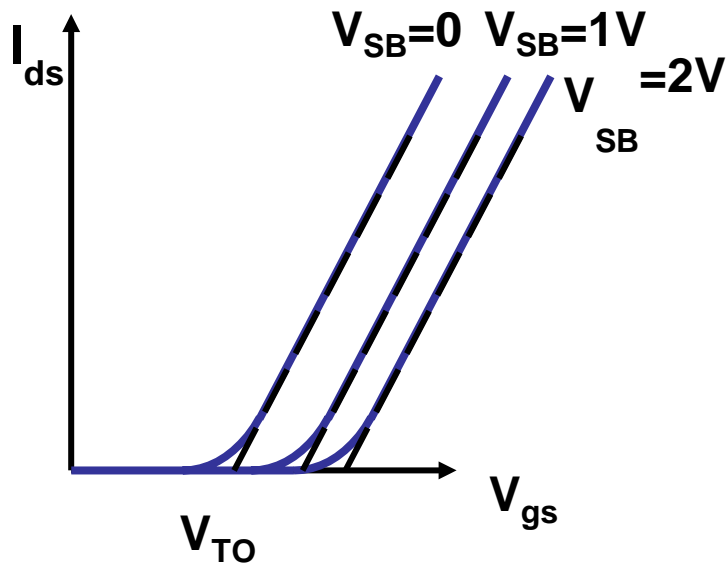
**Threshold Voltage:**  $V_T = V_{FB} + 2 [\phi_p] + \frac{1}{C'_{ox}} \sqrt{2 \epsilon_s q N_A (2[\phi_p] + V_{sb})}$   
p-type substrate

**Threshold Voltage:**  $V_T = V_{FB} - 2 [\phi_n] - \frac{1}{C'_{ox}} \sqrt{2 \epsilon_s q N_D (2[\phi_n] + V_{bs})}$   
n-type substrate



# BACK-BIASING EFFECTS – GAMMA

Body Effect coefficient GAMMA or  $\gamma$  :



$$\gamma = \frac{1}{C'_{ox}} \sqrt{2q\epsilon_{si}N_{sub}}$$

$$V_T = \Phi_{MS} - \frac{Q_{ss}}{C'_{ox}} + 2\phi_F + \gamma$$

$$\epsilon_o = 8.8eE-14F/cm \quad q = 1.6E-19$$

## ***VT ADJUST IMPLANT***

The threshold voltage can be adjusted with an ion implant. If total implant dose is shallow (within  $W_{dmax}$ ) then the change in  $V_t$  is:

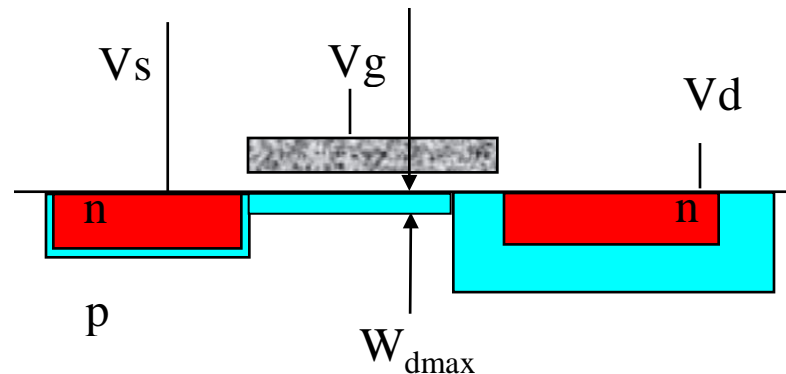
$$\pm \Delta V_t = q \text{ Dose}^* / C_{ox}'$$

Boron gives + shift      where  $\text{Dose}^*$  is the dose that is added to the Si  
 $C_{ox}'$  is gate oxide capacitance/cm<sup>2</sup>

Phosphorous gives - shift       $C_{ox}' = \epsilon_0 \epsilon_r / X_{ox}$

Maximum Depletion Width:

$$W_{dmax} = \sqrt{\frac{4 \epsilon_s [\phi_p]}{qN}}$$

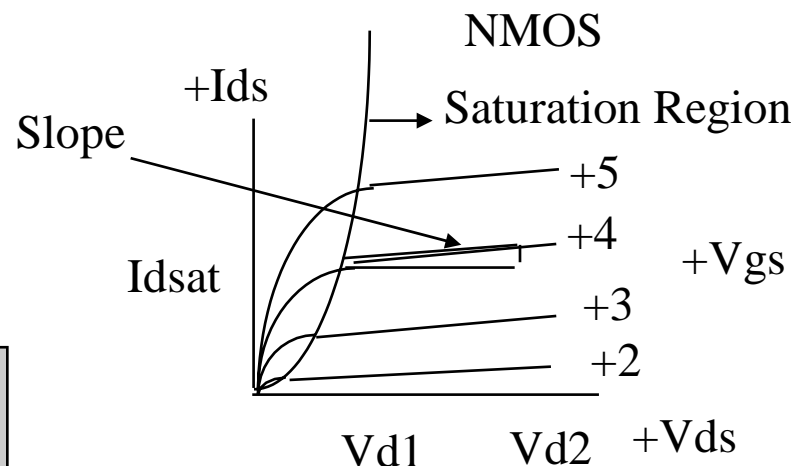
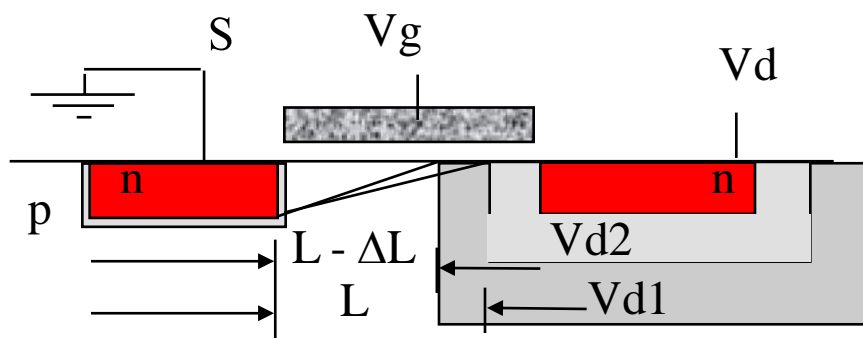


# CHANNEL LENGTH MODULATION - LAMBDA

Channel Length Modulation

Parameter  $\lambda$

$\lambda = \text{Slope} / I_{\text{dsat}}$



$$I_{\text{Dsat}} = \frac{\mu W C_{\text{ox}}' (V_{\text{g}} - V_{\text{t}})^2}{2L} (1 + \lambda V_{\text{ds}})$$

Saturation Region

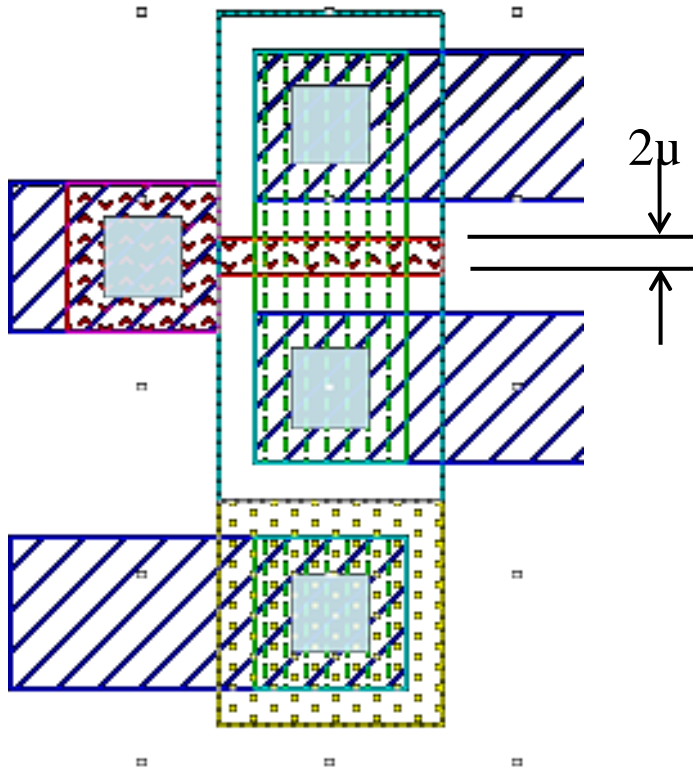
$$I_{\text{D}} = \frac{\mu W C_{\text{ox}}' (V_{\text{g}} - V_{\text{t}} - V_{\text{d}}/2) V_{\text{d}}}{L} (1 + \lambda V_{\text{ds}})$$

Non Saturation Region

NMOS Transistor

DC Model,  $\lambda$  is the channel length modulation parameter and is different for each channel length,  $L$ . Typical value might be 0.02

# TRANSISTOR PROPERTIES OR ATTRIBUTES



$$L = 2u$$

$$W = 8u$$

$$A_d = 8u \times 10u = 80p$$

$$A_s = A_d = 80p$$

$$P_d = 8u + 10u + 8u + 10u = 36u$$

$$P_s = P_d = 36u$$

$$N_{rs} = 1$$

$$N_{rd} = 1$$

NMOS 2/8

## ***LTSPICE MOSFET ATTRIBUTES***

MOSFETS are four terminal devices (Drain, Gate, Source and Substrate).  $L$  and  $W$  are channel length and width in meters,  $A_d$  and  $A_s$  are area of drain and source in square meters. If not specified default values are used. (see next page) Perimeter of Drain and source ( $P_D$  and  $P_S$ ) in meters is used to calculate drain and source side wall capacitance. If  $P_D$  and  $P_S$  are not given the default is zero.  $N_{RD}$  and  $N_{RS}$  are multiplied by the drain and source sheet resistance to give series resistance  $R_D$  and  $R_S$ . The default value for  $N_{RD}$  and  $N_{RS}$  is one.

# MOSFET DEFINITION - LTSPICE

For example:

- \* SPICE Input File
- \* MOSFET names start with M.... **M2** is the name for the MOSFET below and its drain, gate, source and substrate is connected to nodes 3,2,0,0 respectively. The model name is **RITSUBN7**.
- \* The parameters/attributes is everything after that.

**M2** 3 2 0 0 **RITSUBN7** L=2U W=16U ad=96e-12 as=96e-12 pd=44e-6 ps=44e-6 nrd=1.0 nrs=1.0

\*  
\*

The image shows an LTSPICE schematic and two dialog boxes. The schematic includes a MOSFET model named M1 with parameters L=2u, W=16u, nrd=.03, and nrs=.03. It also shows two DC voltage sources, V1 and V2, and a .dc sweep command. The Monolithic MOSFET - M1 dialog box shows the model name RITsubn7 and various physical parameters. The Component Attribute Editor shows the attributes for the MOSFET model, including Prefix, InstName, SpiceModel, Value, Value2, SpiceLine, and SpiceLine2.

**Monolithic MOSFET - M1**

Attribute	Value	Vis.
Prefix	MN	X
InstName	M1	X
SpiceModel	RITSUBN7	X
Value	L=2u W=16u nrd=.03 nrs=.03	X
Value2		
SpiceLine		
SpiceLine2		

LTSPICE schematic showing **.Include** and **.dc** sweep commands. Properties dialog box to define L and W values. Note: attributes with no entry field **nrs** and **nrd** are typed in bottom box. Attribute Editor (CTRL R-click on the transistor) allows attributes with Vis.=X to be displayed on the schematic.

# MOSFET DEFINITION - PSPICE

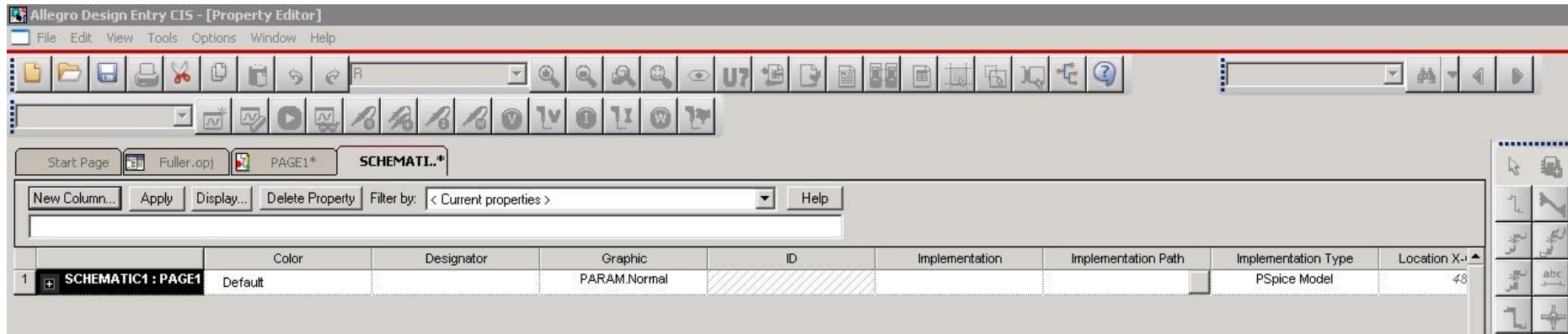
**For example:**

- \* SPICE Input File
- \* MOSFET names start with M.... **M2** is the name for the MOSFET below and its drain, gate, source and substrate is connected to nodes 3,2,0,0 respectively. The model name is **RITSUBN7**.
- \* The parameters/attributes is everything after that.

**M2** 3 2 0 0 **RITSUBN7** L=2U W=16U ad=96e-12 as=96e-12 pd=44e-6 ps=44e-6 nrd=1.0 nrs=1.0

\*

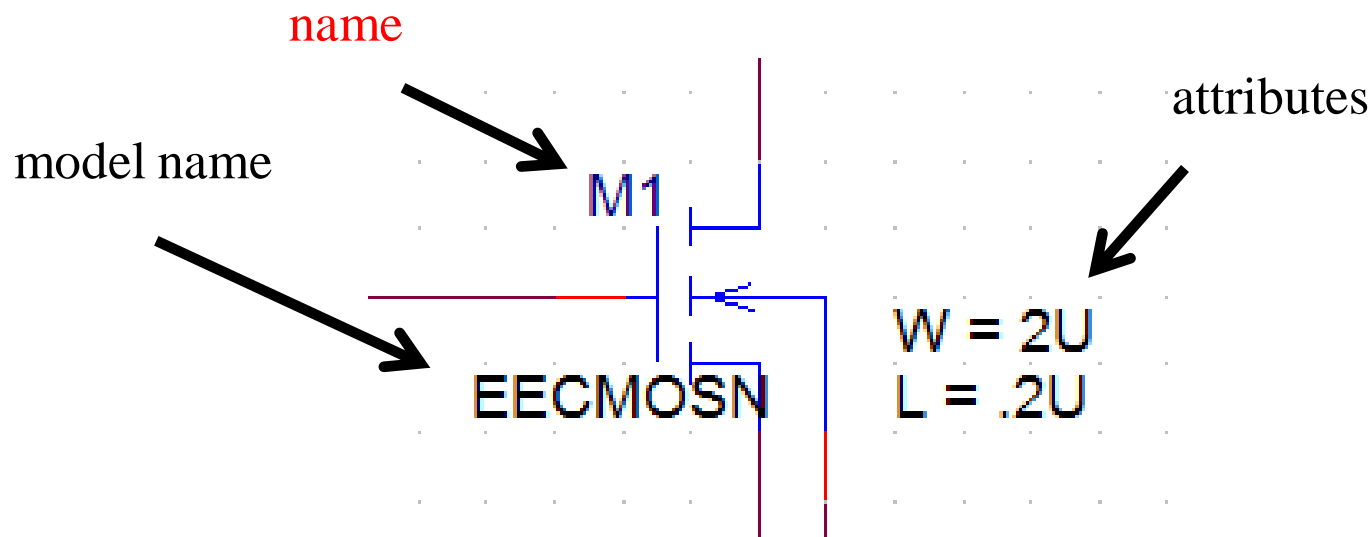
\*



In PSPICE the Attribute Editor (CTRL R-click on the transistor) allows attributes values to be set, new attribute columns to be created, and attributes can be selected to be displayed on the schematic..

## ***MOSFET DEFINITION - PSPICE***

In SPICE a transistor is defined by its **name** and associated **properties or attributes** and its **model**. MOSFET names start with M, attributes (L, W, Ad, As, etc.) are specified by the user and shown in the input file net list. Some attributes can be displayed on the schematic. The model is specified in a file in a given location or is defined in a library.





# ***SIMPLE AND ADVANCED SPICE MODELS***

\* From Electronics II EEEE482 FOR ~100nm Technology

```
.model EECMOSN NMOS (LEVEL=8  
+VERSION=3.1 CAPMOD=2 MOBMOD=1  
+TOX=5E-9 XJ=1.84E-7 NCH=1E17 NSUB=5E16 XT=5E-8  
+VTH0=0.4 U0= 200 WINT=1E-8 LINT=1E-8  
+NGATE=5E20 RSH=1000 JS=3.23E-8 JSW=3.23E-8 CJ=6.8E-4 MJ=0.5 PB=0.95  
+CJSW=1.26E-10 MJSW=0.5 PBSW=0.95 PCLM=5  
+CGSO=3.4E-10 CGDO=3.4E-10 CGBO=5.75E-10)
```

\*

\* From Electronics II EEEE482 FOR ~100nm Technology

```
.model EECMOSP PMOS (LEVEL=8  
+TOX=5E-9 XJ=0.05E-6 NCH=1E17 NSUB=5E16 XT=5E-8  
+VTH0=-0.4 U0= 100 WINT=1E-8 LINT=1E-8  
+NGATE=5E20 RSH=1000 JS=3.51E-8 JSW=3.51E-8 CJ=5.28E-4 MJ=0.5 PB=0.94  
+CJSW=1.19E-10 MJSW=0.5 PBSW=0.94 PCLM=5  
+CGSO=4.5E-10 CGDO=4.5E-10 CGBO=5.75E-10)
```

\*

\* From Electronics II EEEE482 SIMPLE MODEL

```
.model EENMOS NMOS (VTO=0.4 KP=432E-6 GAMMA=0.2 PHI=.88)
```

\*

\* From Electronics II EEEE482 SIMPLE MODEL

```
.model EEPMOS PMOS (VTO=-0.4 KP=122E-6 GAMMA=0.2 PHI=.88)
```

# CHANGING THE MOSFET SPICE MODEL IN PSPICE

**FullerMOSFET.lib:Mbreakn - AMS Model Editor - [Model Text]**

File Edit View Model Plot Tools Window Help

Models List

Model Name	Type
Mbreakn	MOS

.model Mbreakn NMOS vto=0.4 kp=432u gamma=0.2 phi=0.88 l=0.1u

Right click and select EDIT SPICE MODEL to type in underlined parameters

L and W shown on the schematic override default values

0Vdc V1

Mbreakn M1

EECMOSN

W = 2U  
L = .2U

0.1 V2

0

View output file to see this listing of spice model parameters including default values for L and W

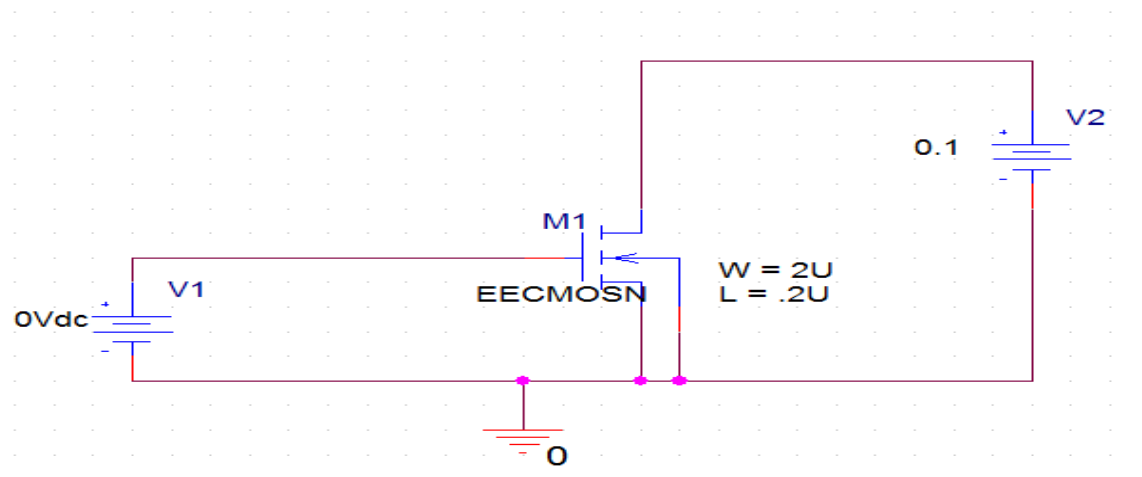
```
62: NMOS
63: LEVEL 1
64: L 100.000000E-09
65: W 100.000000E-06
66: VTO .4
67: KP 432.000000E-06
68: GAMMA .2
69: PHI .88
70: LAMBDA 0
71: IS 10.000000E-15
72: JS 0
73: PB .8
74: PBSW .8
75: CJ 0
76: CJSW 0
77: CGSO 0
78: CGDO 0
79: CGBO 0
80: TOX 0
81: XJ 0
82: UCRIT 10.000000E+03
83: DIOMOD 1
84: VFB 0
85: LETA 0
86: WETA 0
87: UO 0
88: TEMP 0
89: VDD 5
90: XPART 0
91:
92:
93:
```

# COMPARISON OF MOSFET CHARACTERISTICS

The circuit shown can be used to see the transistor family of  $I_{ds}$ - $V_{ds}$  curves,  $I_{ds}$ - $V_{gs}$  plot and  $I_{ds}$ - $V_{gs}$  ( $I_{ds}$  on log scale) Subthreshold plot. We can investigate the effect of changing attributes, SPICE model and model parameters.

V1 is stepped to get family of curves or isswept to get  $I_{ds}$ - $V_{gs}$  and Sub- $V_t$  plots

V2 is swept to get family of curves or isheld constant to get  $I_{ds}$ - $V_{gs}$  plots



# PSPICE MOSFET MODEL PARAMETERS

95 mosfet model parameters used by  
cadence PSPICE for **Level 8** BSIM

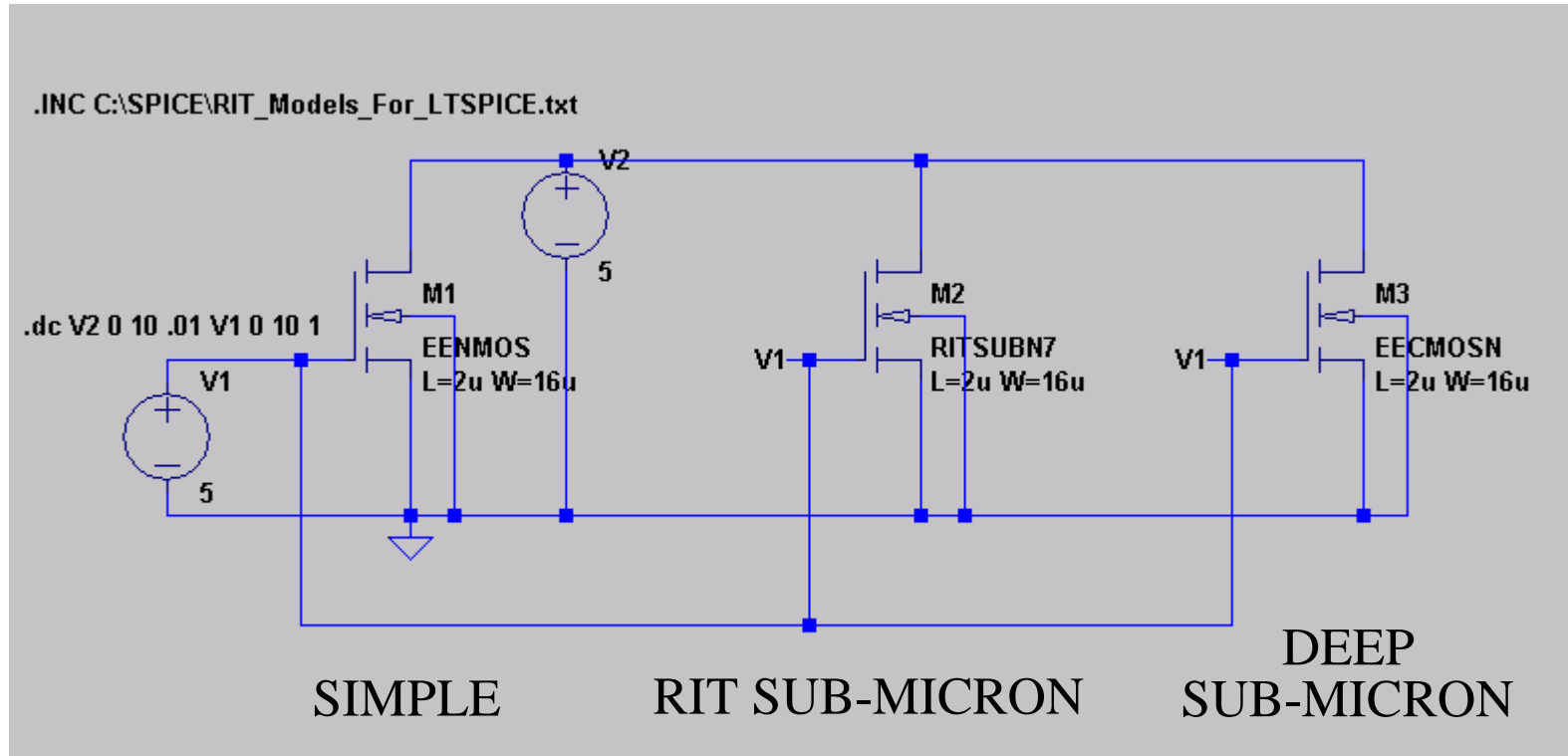
Start Page	FullerMOS..*	PAGE1*
280:	EECMOSP	
281:	PMOS	
282:	LEVEL 8	
283:	L 100.000000E-06	
284:	W 100.000000E-06	
285:	VTC -.4	
286:	KP 414.377300E-06	
287:	GAMMA 0	
288:	PHI	
289:	LAMBDA 0	
290:	RSH 1.000000E+03	
291:	IS 1.000000E-15	
292:	JS 35.100000E-09	
293:	JSSW 35.100000E-09	
294:	PB .94	
295:	PBSW .94	
296:	CJ 528.000000E-06	
297:	CJSW 119.000000E-12	
298:	MJSW .5	
299:	CGSC 450.000000E-12	
300:	CGDC 450.000000E-12	
301:	CGBC 575.000000E-12	
302:	NSUB 50.000000E+15	
303:	TOX 5.000000E-09	
304:	XJ 50.000000E-09	
305:	UCRIT 10.000000E+03	
306:	DIOMOD 1	
307:	VFB -1	
308:	LETA 0	
309:	WETA 0	
310:	UO 100	
311:	TEMP	
312:	VDD	
313:	XPART 0	
314:	VTIHO -.4	
315:	UA 1.000000E-09	
316:	UB 100.000000E-21	
317:	UC -46.500000E-12	
318:	VSAT 80.000000E+03	
319:	RDSW 200	
320:	VOFF -.08	
321:	PCLM 5	
322:	A0 1	
323:	A1 0	
324:	A2 1	
325:	NPEAK 100.000000E+15	
326:	XT 50.000000E-09	
327:	LDD 0	
328:	LITL 27.386130E-09	
329:	UA1 1.000000E-09	
330:	UB1 -1.000000E-18	
331:	UC1 .025	
332:	DSUB .56	
333:	NGATE 500.000000E+18	
334:	MOBMOD 0	
335:	PRWG 1	
336:	LINT 10.000000E-09	
337:	WINT 10.000000E-09	
338:	DLC 10.000000E-09	
339:	DWC 10.000000E-09	
340:	CF 107.725800E-12	
341:	NOIA 9.900001E+18	
342:	NOIB 2.400000E+03	
343:	NOIC 1.400000E-12	
344:	VERSION 4.1	
345:	PBSWG .94	
346:	MJSWG .5	
347:	CJSWG 119.000000E-12	
348:	JTSCD 35.100000E-09	
349:	JSTSCD 35.100000E-09	
350:	TOXM 3.000000E-09	
351:	LLC 0	
352:	LWC 0	
353:	LWLC 0	
354:	WLC 0	
355:	WWC 0	
356:	WWLC 0	
357:	BSIM4oxideTrapDensityC 8.750000E+09	
358:	toxp 3.000000E-09	
359:	eu 1	
360:	aigc .31	
361:	bigc .024	
362:	cigc .03	
363:	aigsd .31	
364:	bigsd .024	
365:	cigsd .03	
366:	dlcig 10.000000E-09	
367:	dwj 10.000000E-09	
368:	CJSWGD 500.000000E-12	
369:	PBSWGD 1	
370:	CJSWGS 500.000000E-12	
371:	PBSWGS 1	
372:	coxe .01151	
373:	coxp .01151	
374:	BSIM4factor1 94.868330E-06	

31 mosfet model parameters used by cadence PSPICE for  
**Level 1** Shichman and Hodges

FullerMOS..*	PAGE1*	ID-VGS-SW...	SCHEMATI..*	ID-VGS-S...
		EENMOS		EEPMS
		NMOS		PMOS
LEVEL		1		1
L		100.000000E-06		100.000000E-06
W		100.000000E-06		100.000000E-06
VTC		.4		-.4
KP		432.000000E-06		122.000000E-06
GAMMA		.2		.2
PHI		.88		.88
LAMBDA		0		0
RSH				
IS		10.000000E-15		10.000000E-15
JS		0		0
JSSW				
PB		.8		.8
PBSW		.8		.8
CJ		0		0
CJSW		0		0
MJSW				
CGSC		0		0
CGDC		0		0
CGBC		0		0
NSUB				
TOX		0		0
XJ		0		0
UCRIT		10.000000E+03		10.000000E+03
DIOMOD		1		1
VFB		0		0
LETA		0		0
WETA		0		0
UO		0		0
TEMP		0		0
VDD		5		5
XPART		0		0

View Output File

# LTSPICE CIRCUIT SCHEMATIC



Three transistor all the same  $L=2\mu$  and  $W=16\mu$  but with different SPICE models. (SIMPLE, RIT SUB-MICRON and 100nm DEEP SUB-MICRON)

## THREE DIFFERENT NMOS SPICE MODELS

From Sub-Micron CMOS Manufacturing Classes in MicroE

```
.MODEL RITSUBN7 NMOS (LEVEL=7  
+VERSION=3.1 CAPMOD=2 MOBMOD=1  
+TOX=1.5E-8 XJ=1.84E-7 NCH=1.45E17 NSUB=5.33E16 XT=8.66E-8  
+VTH0=1.0 U0= 600 WINT=2.0E-7 LINT=1E-7  
+NGATE=5E20 RSH=1082 JS=3.23E-8 JSW=3.23E-8 CJ=6.8E-4 MJ=0.5 PB=0.95  
+CJSW=1.26E-10 MJSW=0.5 PBSW=0.95 PCLM=5  
+CGSO=3.4E-10 CGDO=3.4E-10 CGBO=5.75E-10)  
*
```

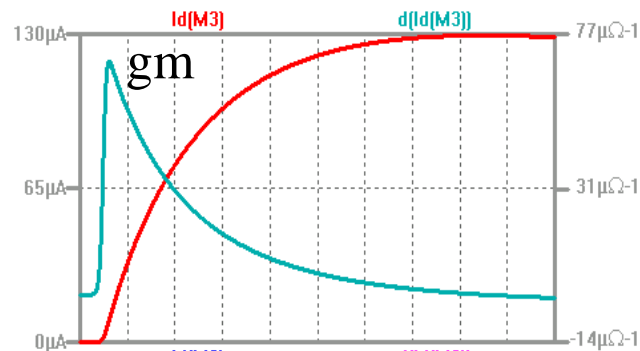
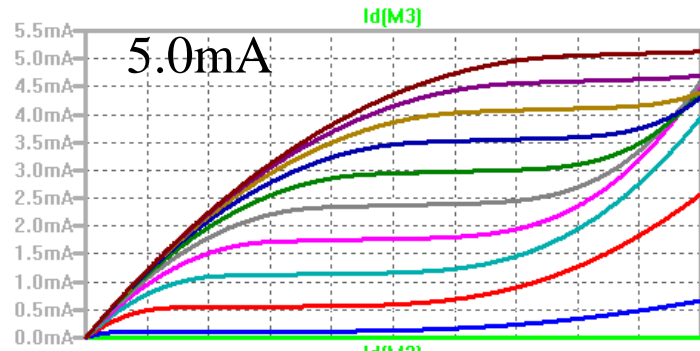
\* From Electronics II EEEE482 FOR ~100nm Technology Deep Sub-Micron

```
.model EECMOSN NMOS (LEVEL=8  
+VERSION=3.1 CAPMOD=2 MOBMOD=1  
+TOX=5E-9 XJ=1.84E-7 NCH=1E17 NSUB=5E16 XT=5E-8  
+VTH0=0.4 U0= 200 WINT=1E-8 LINT=1E-8  
+NGATE=5E20 RSH=1000 JS=3.23E-8 JSW=3.23E-8 CJ=6.8E-4 MJ=0.5 PB=0.95  
+CJSW=1.26E-10 MJSW=0.5 PBSW=0.95 PCLM=5  
+CGSO=3.4E-10 CGDO=3.4E-10 CGBO=5.75E-10)  
*
```

\* From Electronics II EEEE482 SIMPLE MODEL

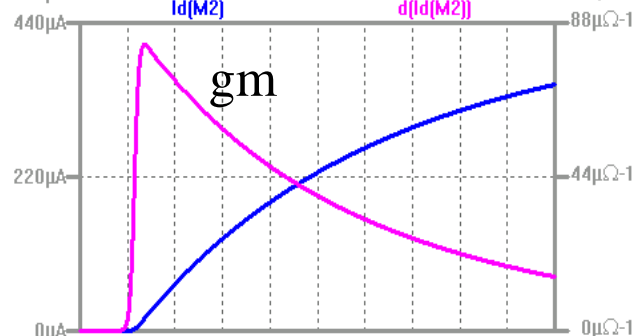
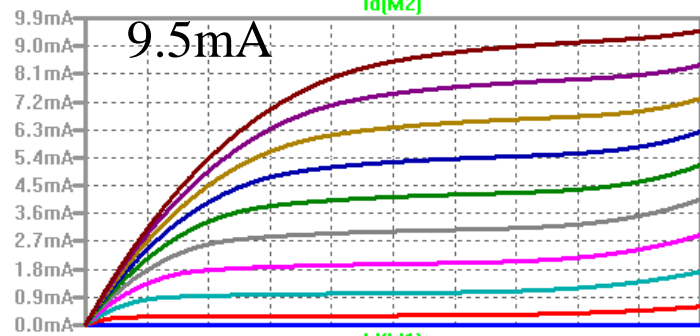
```
.model EENMOS NMOS (VTO=0.4 KP=432E-6 GAMMA=0.2 PHI=.88)
```

# LTSPICE OUTPUT FOR ID-VDS AND ID-VG



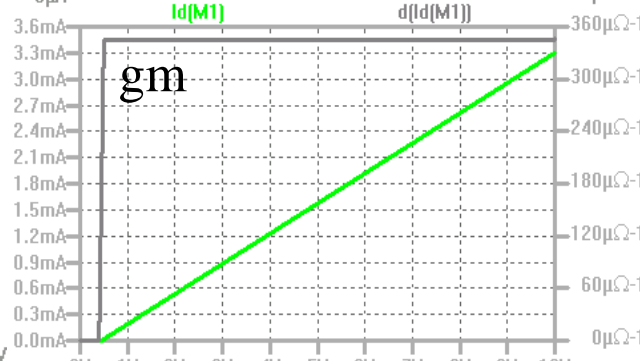
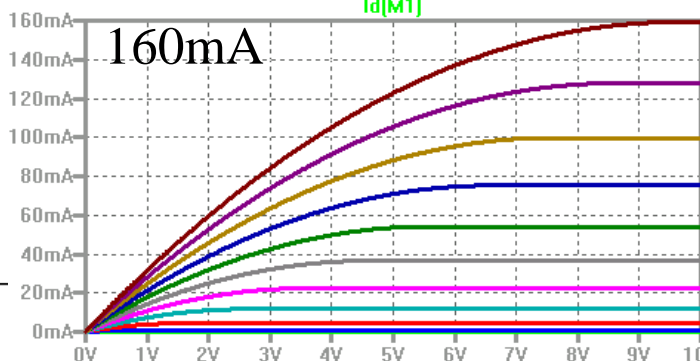
Model is EECMOSN  
L=2u W=16u

Model not good.  
Current low and only  
good out to 3 volts.



Model is RITSUBN7  
L=2u W=16u

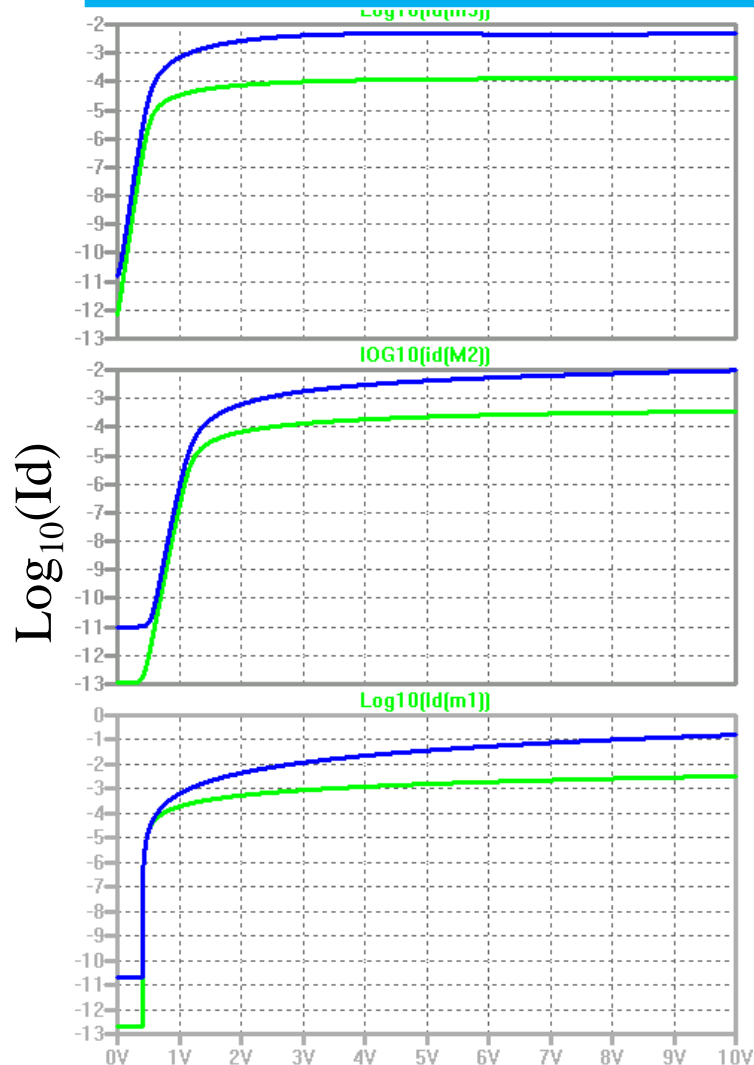
Model good for RIT  
Sub-Micron MOSFETs



Model is EENMOS  
L=2u W=16u

Model not good current  
too large

# LTSPICE OUTPUT FOR SUBTHRESHOLD ID-VGS



Model is EECMOSN  
L=2u W=16u

Model not good MOSFET does not turn off,  $V_t$  too low

Model is RITSUBN7  
L=2u W=16u

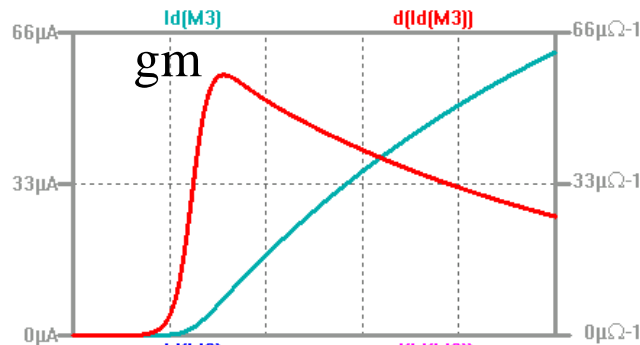
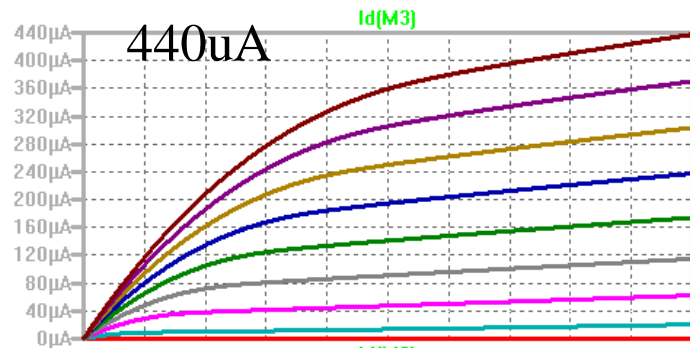
Model good

Model is EENMOS  
L=2u W=16u

Model incorrect in subthreshold region.  
Subthreshold slope not possible.

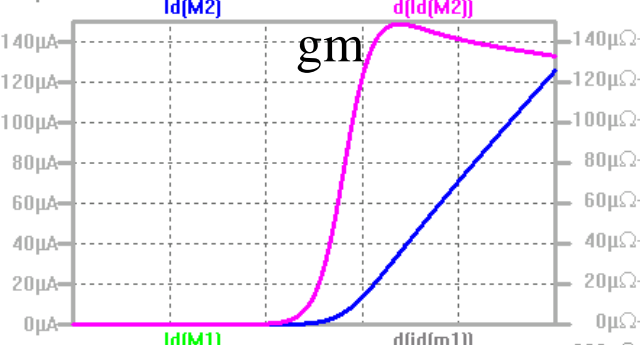
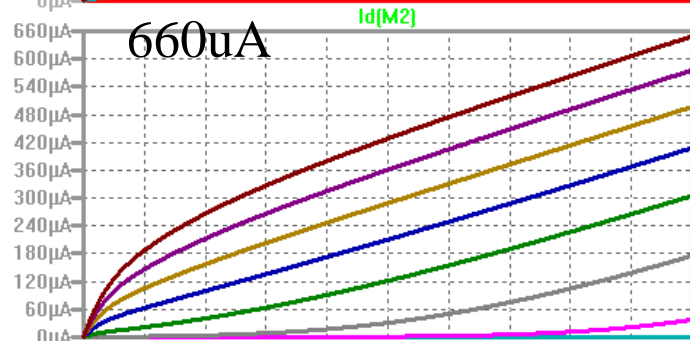


# DEEP SUB-MICRON TRANSISTOR MODELS



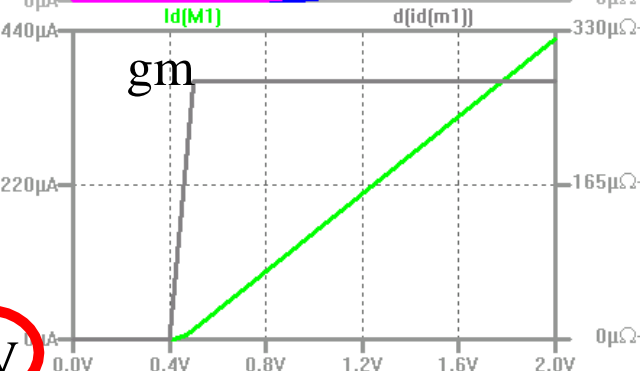
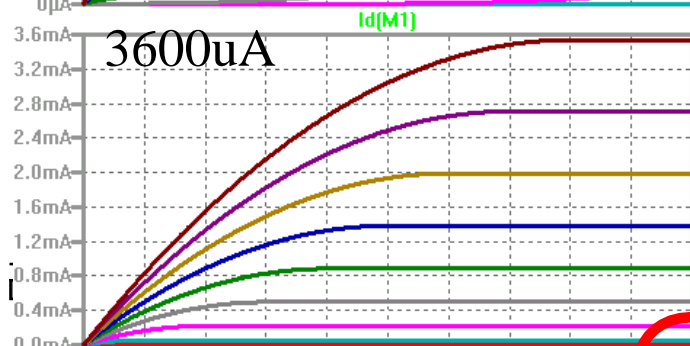
Model is EECMOSN  
 $L=0.25\mu$   $W=1.6\mu$

Model good for Deep  
 Sub-Micron MOSFETs



Model is RITSUBN7  
 $L=0.25\mu$   $W=1.6\mu$

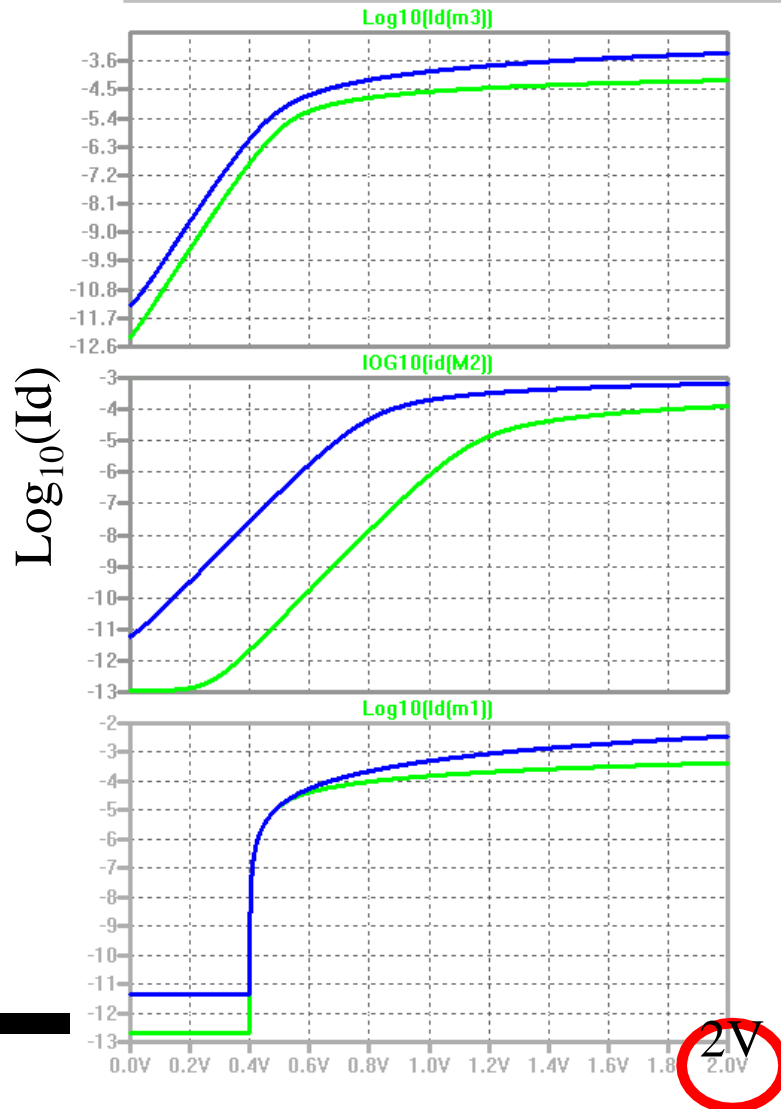
Model not good too  
 much short channel  
 effects



Model is EENMOS  
 $L=0.25\mu$   $W=1.6\mu$

Model not good current  
 too large does not show  
 mobility degradation

# DEEP SUB-MICRON TRANSISTOR MODELS



Model is EECMOSN  
 $L=0.25\mu$   $W=1.6\mu$

Model good for Deep Sub-Micron MOSFETs

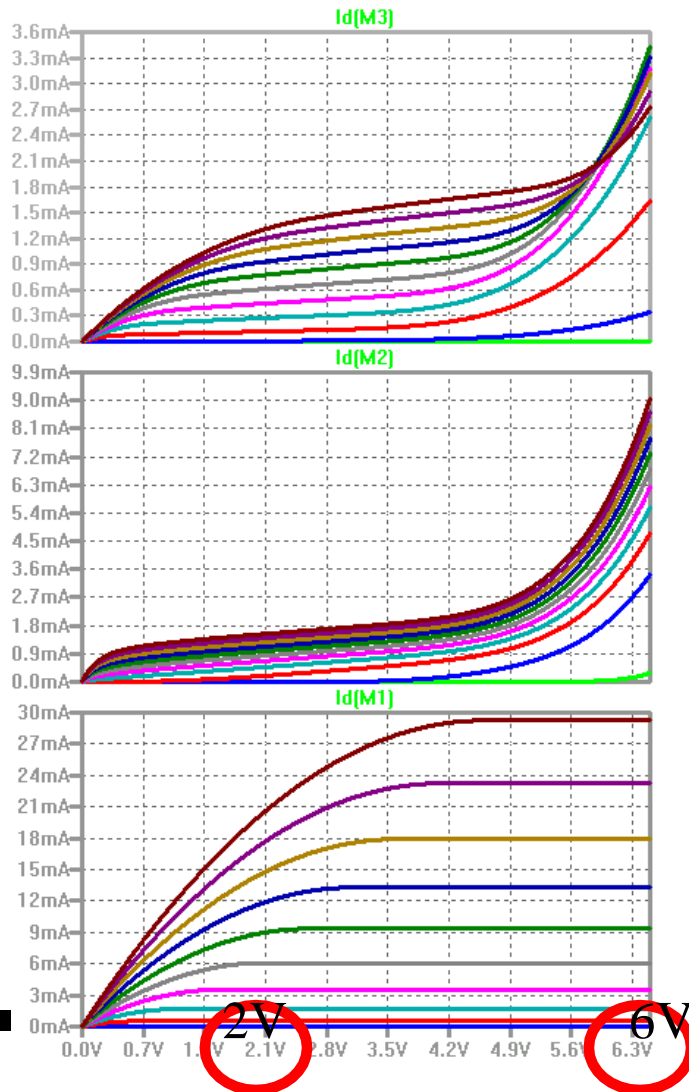
Model is RITSUBN7  
 $L=0.25\mu$   $W=1.6\mu$

Model not good too much DIBL

Model is EENMOS  
 $L=0.25\mu$   $W=1.6\mu$

Model incorrect in subthreshold region

# DEEP SUB-MICRON TRANSISTOR MODELS



Deep sub-micron transistors show punch through at drain voltages over 3.3 volts. Which is correct.

Problem is worse in the sub-micron transistor because the channel is lighter doped.

Simple model is incorrect.

# ***MOSFET MODELS USED BY LTSPICE***

LTSPICE uses several different types of MOSFET models including simple, deep submicrometer, Silicon On Insulator (SOI), Vertical double diffused Power MOSFET. Level = 1 is the default if a model level is not specified.

Level

- |    |  |   |                                   |
|----|--|---|-----------------------------------|
| 1  | Shichman and Hodges                                      | } | 1 <sup>st</sup> generation models |
| 2  | MOS2, Vladimirescu and Liu, UC Berkeley, October 1980    |   |                                   |
| 3  | MOS3, a semi-empirical model, UC Berkeley                |   |                                   |
| 4  | BSIM UC Berkeley, May 1985                               | } | 2 <sup>nd</sup> generation models |
| 5  | BSIM2, UC Berkeley, October 1990                         |   |                                   |
| 6  | MOS6, UC Berkeley, March 1990                            |   |                                   |
| 8  | BSIM3V3.3.0, UC Berkeley 2005                            |   |                                   |
| 9  | BSIMSOI3.2, Silicon on Insulator (SOI), UC Berkeley 2004 | } | 3 <sup>rd</sup> generation models |
| 14 | BSIM4.6.1, UC Berkeley 2007                              |   |                                   |
|    | more....   |   |                                   |

# ***SIMPLE AND ADVANCED SPICE MODEL***

\* From Electronics II EEEE482 FOR ~100nm Technology

```
.model EECMOSN NMOS (LEVEL=8  
+VERSION=3.1 CAPMOD=2 MOBMOD=1  
+TOX=5E-9 XJ=1.84E-7 NCH=1E17 NSUB=5E16 XT=5E-8  
+VTH0=0.4 U0= 200 WINT=1E-8 LINT=1E-8  
+NGATE=5E20 RSH=1000 JS=3.23E-8 JSW=3.23E-8 CJ=6.8E-4 MJ=0.5 PB=0.95  
+CJSW=1.26E-10 MJSW=0.5 PBSW=0.95 PCLM=5  
+CGSO=3.4E-10 CGDO=3.4E-10 CGBO=5.75E-10)
```

\*

\* From Electronics II EEEE482 FOR ~100nm Technology

```
.model EECMOSP PMOS (LEVEL=8  
+TOX=5E-9 XJ=0.05E-6 NCH=1E17 NSUB=5E16 XT=5E-8  
+VTH0=-0.4 U0= 100 WINT=1E-8 LINT=1E-8  
+NGATE=5E20 RSH=1000 JS=3.51E-8 JSW=3.51E-8 CJ=5.28E-4 MJ=0.5 PB=0.94  
+CJSW=1.19E-10 MJSW=0.5 PBSW=0.94 PCLM=5  
+CGSO=4.5E-10 CGDO=4.5E-10 CGBO=5.75E-10)
```

\*

\* From Electronics II EEEE482 SIMPLE MODEL

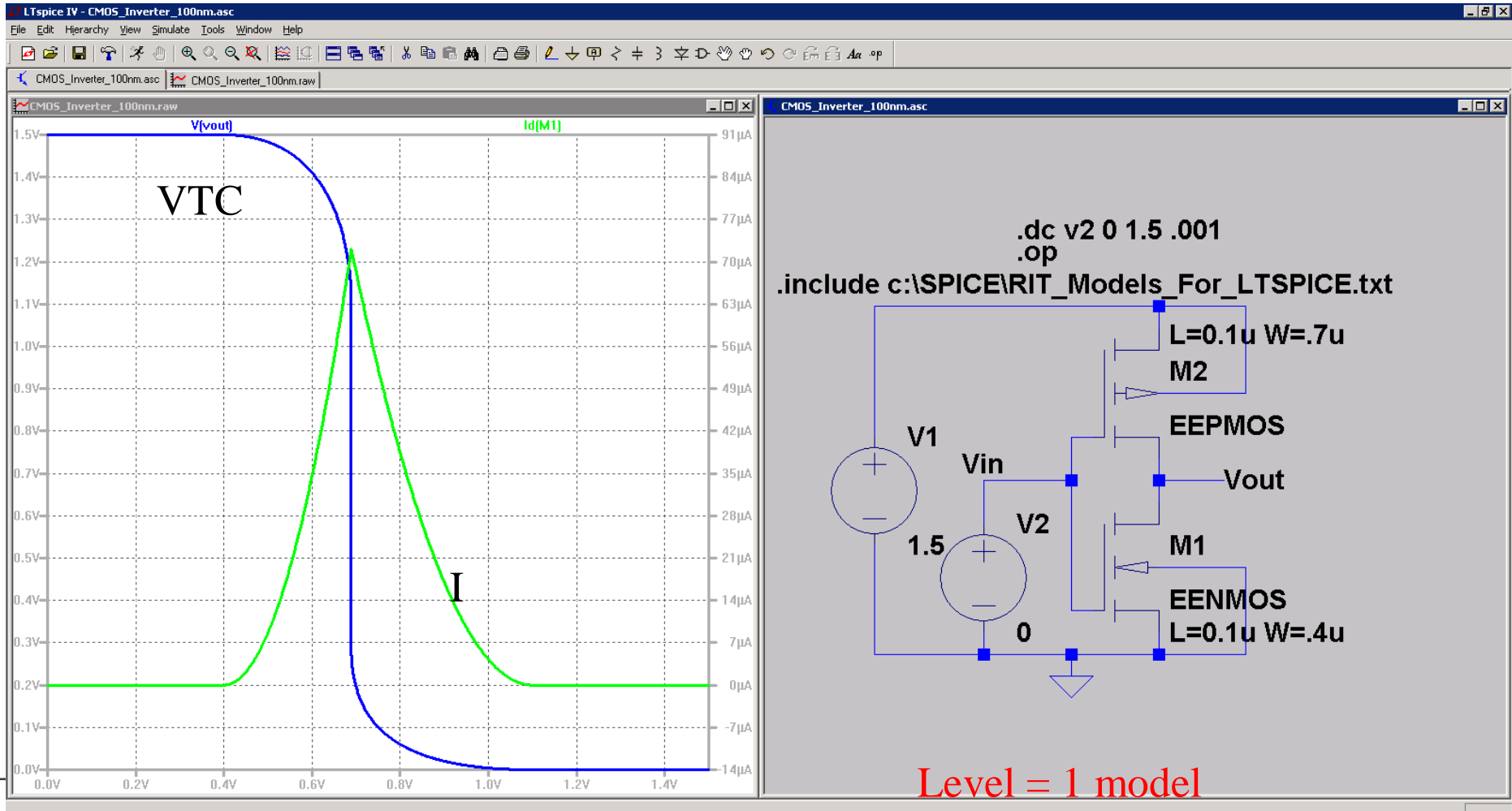
```
.model EENMOS NMOS (VTO=0.4 KP=432E-6 GAMMA=0.2 PHI=.88)
```

\*

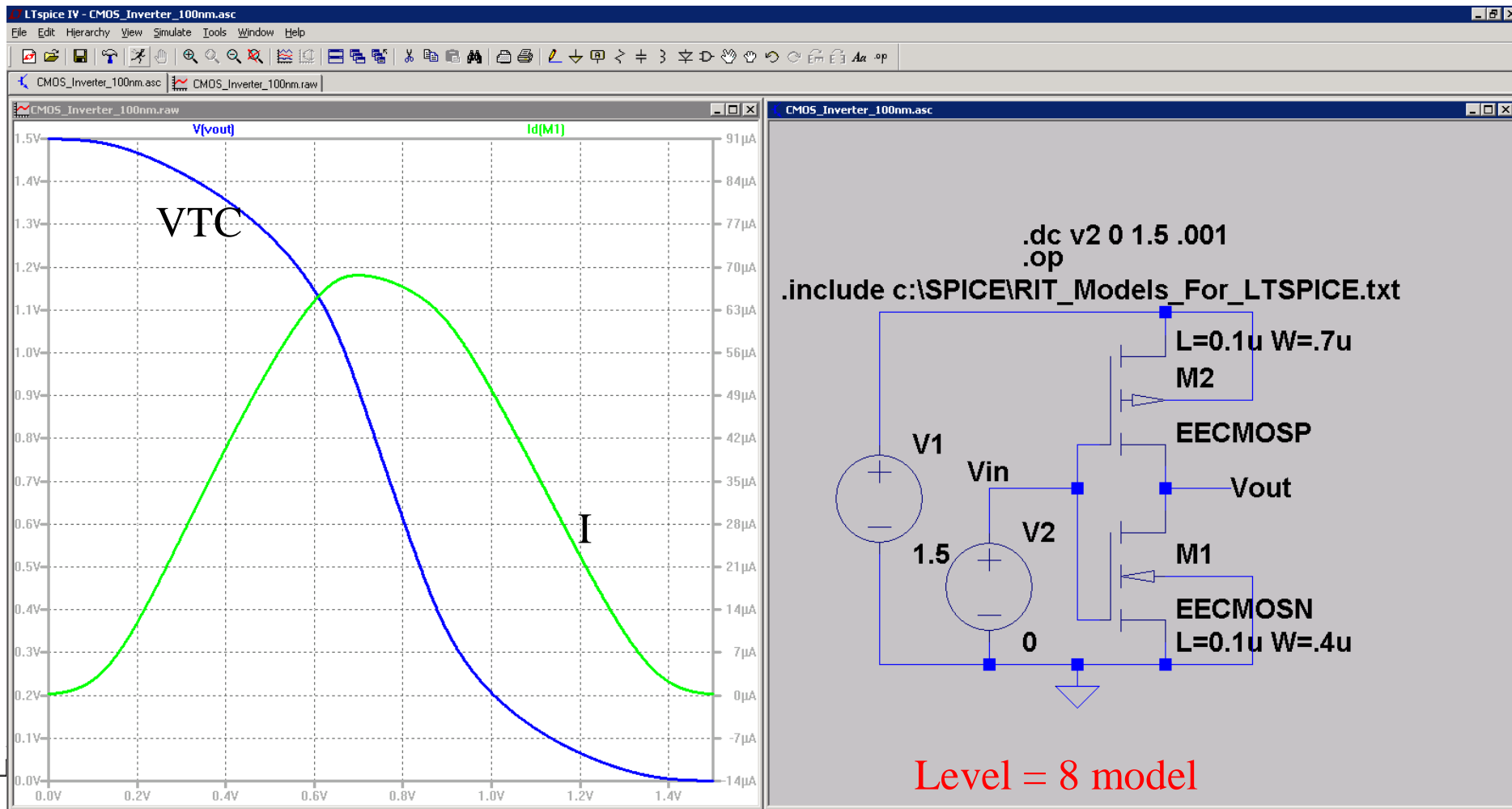
\* From Electronics II EEEE482 SIMPLE MODEL

```
.model EEPMOS PMOS (VTO=-0.4 KP=122E-6 GAMMA=0.2 PHI=.88)
```

# CMOS INVERTER WITH LEVEL 1 SPICE MODEL



# CMOS INVERTER WITH LEVEL 8 SPICE MODEL



## ***CONCLUSION***

All of these examples are for DC characteristics but similar results would be shown for examples that depend on internal capacitors and resistors such as a study of rise-time, fall time, gate delay, oscillators, multi-vibrators, etc.

In general the third generation SPICE models for MOSFETS give better results.

Level=1 models are not good for MOSFETS with  $L$  less than 10 $\mu\text{m}$ .

Large MOSFETS, SUB-MICRON MOSFETS and DEEP SUB MICRON MOSFET models have been introduced.



## ***REFERENCES***

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2. Operation and Modeling of the MOS Transistor, 2nd Edition, Yannis Tsividis, 1999, McGraw-Hill, ISBN-0-07-065523-5
3. UTMOST III Modeling Manual-Vol.1. Ch. 5. From Silvaco International.
4. ATHENA USERS Manual, From Silvaco International.
5. ATLAS USERS Manual, From Silvaco International.
6. Device Electronics for Integrated Circuits, Richard Muller and Theodore Kamins, with Mansun Chan, 3<sup>rd</sup> Edition, John Wiley, 2003, ISBN 0-471-59398-2
7. ICCAP Manual, Hewlet Packard
8. PSpice Users Guide.